

### IN THE CLAIMS

This listing of claims replaces all prior listings

#### Listing of Claims:

1. (Currently Amended) Method of manufacturing a diffusing reflector comprising the processes of:  
preparing ~~for~~ a substrate;  
forming a first resin film having photosensitivity on said substrate;  
providing gathering of pillar-shaped bodies isolated from each other through patterning of said resin film with the photolithography;  
~~forming uneven surface layer having the maximum inclination angle of under  $12^{\circ}$  by~~  
~~gently deforming gently individual~~ said pillar-shaped bodies through the a reflow;  
forming an uneven surface layer having the maximum inclination angle of under  $12^{\circ}$  by  
coating said gently deformed pillar-shaped bodies and covering open flat spaces located between  
said isolated pillar-shaped bodies with a second resin, thereby minimizing an occurrence of a flat  
surface area on said substrate; and  
forming a metal film on ~~gathering of~~ said ~~gently deformed~~ uneven surface layer.
2. (Original) Method of manufacturing a diffusing reflector as claimed in claim 1, wherein said maximum inclination angle is about  $10^{\circ}$ .
3. (Cancelled)
4. (Currently Amended) Method of manufacturing a diffusing reflector as claimed in claim 1, wherein said reflow process is the a heat treatment under the temperature of about  $220^{\circ}\text{C}$ .
5. (Currently Amended) Method of manufacturing a diffusing reflector as claimed in claim 1, wherein gathering of polygonal pillar-shaped bodies isolated each other by the divided patterning of said first resin film by said photolithography is provided.

6. (Currently Amended) Method of manufacturing a diffusing reflector as claimed in claim 5, wherein said first resin film is patterned by the divided patterning means so that size of gap between said polygonal pillar-shaped bodies isolated each other is almost equal to ~~the~~ a minimum resolution of photolithography.